CLAIMS

[Claim 1]

A liquid discharge apparatus, comprising:

a head having a discharge port surface in which a plurality of discharge port arrays are provided, each discharge port array including a plurality of discharge ports which discharge liquid and are arranged along a first direction, the plurality of discharge port arrays include a first discharge port array and a second discharge port array which is adjacent to the first discharge port array;

a suction port performing a suction operation for the discharge port surface; and

a moving unit causing the suction port to move in a second direction which intersects the first direction under a state in which the suction port is spaced away from the discharge port surface,

wherein the discharge ports of the first discharge port array and the discharge ports of the second discharge port array are arranged so as not to overlap each other in the first direction.

[Claim 2]

A liquid discharge apparatus according to claim 1, wherein the plurality of discharge port arrays further include a third discharge port array which is adjacent to the second discharge port array, and a fourth discharge port array which is adjacent to the third discharge port array, and

wherein the first discharge port array, the second discharge port array, the third discharge port array, and the fourth discharge port array are arranged so as not to overlap each other in the first direction.

[Claim 3]

A liquid discharge apparatus according to claim 1, wherein a length of the suction port is larger than a length of each of the plurality of discharge port arrays.

[Claim 4]

A liquid discharge apparatus according to claim 1,

wherein the suction port is configured to suck the liquid from the first discharge port array, then to suck the liquid from the second discharge port array, and

wherein a portion of the suction port, which passes through a position opposed to each of the plurality of discharge ports of the first discharge port array, and a portion of the suction port, which passes through a position opposed to each of the plurality of discharge ports of the second discharge port array, are different from each other.

[Claim 5]

A liquid discharge apparatus according to claim 4, wherein the portion of the suction port, which has passed through the position opposed to the each of the plurality of discharge ports of the first discharge port array, passes through a position other than the position opposed to the each of the plurality of discharge ports of the second discharge port array.

[Claim 6]

A liquid discharge apparatus according to claim 1,

wherein the second direction is orthogonal to the first direction.

[Claim 7]
A liquid discharge apparatus according to claim 1,
wherein the second direction inclines with respect to a direction orthogonal to the first direction.

[Claim 8]
A liquid discharge apparatus according to claim 1, further comprising a blow port which is disposed behind the suction port in the second direction so as to be inclined toward the discharge port surface, and blow gas to the discharge port surface.

[Claim 9]
A liquid discharge apparatus according to claim 8, further comprising a pressure control unit controlling a pressure in one of the suction port and the blow port.

[Claim 10]
An imprint apparatus, comprising:
a head having a discharge port surface in which a plurality of discharge port arrays are provided, each discharge port array including a plurality of discharge ports which discharge liquid and are arranged along a first direction, the plurality of discharge port arrays include a first discharge port array and a second discharge port array which is adjacent to the first discharge port array;
a suction port performing a suction operation for the discharge port surface;
a moving unit causing the suction port to move in a second direction which intersects the first direction under a state in which the suction port is spaced away from the discharge port

surface, wherein the discharge ports of the first discharge port array and the discharge ports of the second discharge port array are arranged so as not to overlap each other in the first direction; and

a patterning unit forming a pattern corresponding to a concavo-convex pattern of a mold on one surface of a substrate by bringing the one surface of the substrate having the liquid discharged thereto with the head and a surface of the mold having the concavo-convex pattern formed thereon into abutment against each other.

[Claim 11]

An imprint apparatus according to claim 10, wherein the liquid has photocurability, and

wherein the patterning unit has a light irradiation unit irradiating the pattern formed on the substrate with light to cure the pattern.

[Claim 12]

A method of manufacturing a component including a substrate through use of an imprint apparatus, the imprint apparatus comprising: a head having a discharge port surface in which a plurality of discharge port arrays are provided, each discharge port array including a plurality of discharge ports which discharge liquid and are arranged along a first direction, the plurality of discharge port arrays include a first discharge port array and a second discharge port array which is adjacent to the first discharge port array; and a suction port, the method comprising:

performing a suction operation for the discharge port surface by moving the suction port in a second direction

intersecting the first direction under a state in which the suction port is spaced away from the discharge port surface, wherein the discharge ports of the first discharge port array and the discharge ports of the second discharge port array are arranged so as not to overlap each other in the first direction;

applying the liquid to a surface of the substrate with the head after the suction operation;

forming a pattern corresponding to a concavo-convex pattern of a mold on the surface of the substrate by bringing the surface of the substrate having the liquid applied thereto and a surface of the mold having the concavo-convex pattern formed thereon into abutment against each other; and

processing the substrate having the pattern formed thereon.